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ABSTRACT:

PURPOSE: To set accurately a gap between a substrate and a mask without touching by a method wherein a distance between the mask and the substrate is detected on a gap measuring apparatus provided on substrate side, and the detected distance is transferred to a gap measuring apparatus provided on mask side.

CONSTITUTION: A plural gap measuring apparatus 7 is enclosed in a substrate base 6. Next, a reference plate 3 is placed on the substrate base 6, the distance is measured and then the gap measuring apparatus 7

is zeroed. Then,
the reference plate 3 is demounted, a mask 1 is brought
near to the substrate
6, and a gap between a reference plane 8 and the substrate
base 6 is measured.
The measured value is set as an initial value of a gap
measuring apparatus 10
on mask side. After that, a maks holder 9 is kept apart
from the substrate
base 6. Next, a wafer with a resist applied thereon is
placed on the substrate
base 6. Then, the mask holder 9 is moved to come near to
the substrate base 6,
a gap to the substrate base 6 is measured on the gap
measuring apparatus 10
until a given value is obtained.

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